

TSMC-01-195CC



May 11, 2004

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

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Subject:

Serial No. 10/823,149 04/13/04

Lain-Jong Li et al.

COMPOSITE ETCHING STOP IN SEMI-
CONDUCTOR PROCESS INTEGRATION

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation
In An Application.

The following Patents and/or Publications are submitted to
comply with the duty of disclosure under CFR 1.97-1.99 and
37 CFR 1.56.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being
deposited with the United States Postal Service as first class
mail in an envelope addressed to: Commissioner for Patents,
P.O. Box 1450, Alexandria, VA 22313-1450, on May 17, 2004.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

 5/17/04

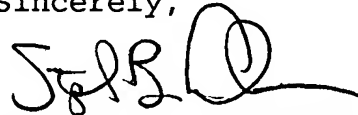
TSMC-01-195CC

U.S. Patent 6,127,262 to Huang et al., "Method and Apparatus for Depositing an Etch Stop Layer," discloses a process for an etch stop layer.

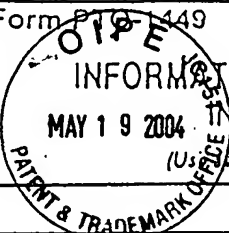
U.S. Patent 6,209,484 to Huang et al., "Method and Apparatus for Depositing an Etch Stop Layer," discloses a process for an etch stop layer.

U.S. Patent 5,585,304 to Hayashi et al., "Method of Making Semiconductor Device with Multiple Transparent Layers," discusses a semiconductor wafer which is comprised of a transparent layer interposed between a thin silicon layer and a thick silicon layer.

Sincerely,

A handwritten signature in black ink, appearing to read 'SBA', with a large circular flourish at the end.

Stephen B. Ackerman,
Reg. No. 37761



INFORMATION DISCLOSURE CITATION IN AN APPLICATION

MAY 19 2004

(Use on several sheets if necessary)

Docket Number (Optional)

TSMC-01-195CC

Application Number

10/823,149

Applicant

Lain-Jong Li et al.

Filing Date

04/13/04

Group Art Unit

U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILED DATE IF APPROPRIATE
	558530	4/12/96	Hayashi et al.	437	62	8/2/94
	612726	2/10/00	Huang et al.	438	634	5/7/97
	6209484	4/3/01	Huang et al.	118	723E	4/17/00

FOREIGN PATENT DOCUMENTS

DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
					YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Part/next Pages, Etc.)

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.